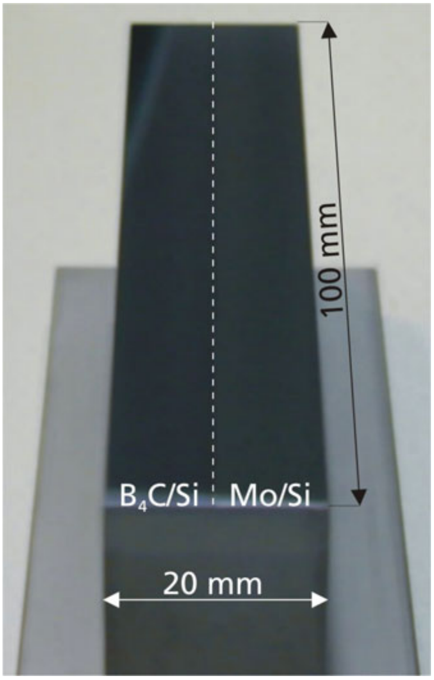
IWS

Fraunhofer Institut
Werkstoff- und
Strahltechnik

Multilayer mirrors for photon energies between 900-1800 eV

Motivation

Depending on the concrete application, EUV and X-Ray optical elements with high reflectance or high resolving powers are required. The opportunity to design custom-tailored nanometer multilayer mirrors enables the choice of both on one mirror surface.



Synchrotron mirrors with reflection coatings for high resolving powers (B_4C/Si) and high reflectances (Mo/Si).

Applications

- Synchrotron optics
- X-Ray fluorescence analysis
- X-Ray spectroscopy
- X-Ray reflectometry
- X-Ray diffractometry

Our offer

- Optimization of multilayer mirrors for specific customer requirements
- Multilayers with high reflectance of up to 65 %
- Multilayers with high resolving powers of up to 500

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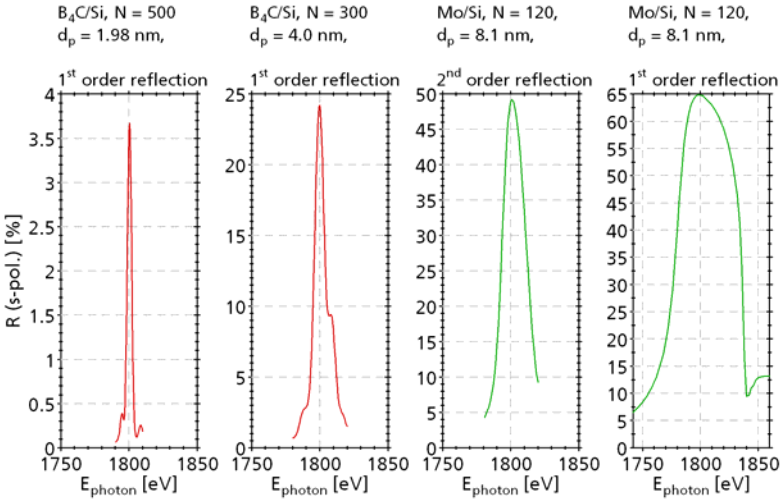

Spectra of B_4C/Si and Mo/Si multilayer mirrors.